WHAT IS CLAIMED IS:

1. A liquid discharge apparatus, comprising:

a head including a discharge port surface on which a discharge port is formed to discharge a liquid;

a first reservoir that stores the liquid to be supplied to the head;

a flexible member, separating an inner space of the first reservoir into a first chamber that stores the liquid and a second chamber that stores an operation liquid;

a second reservoir communicating with the second chamber, the second reservoir storing the operation liquid to be supplied to the second chamber, the second reservoir being in such a manner that a liquid surface of the operation liquid stored in the second reservoir is positioned below the discharge port surface; and

an adjustment unit that performs adjustment in such a manner that a position of the liquid surface of the operation liquid in the second reservoir falls within a predetermined range in a state where the second reservoir is opened to atmosphere.

2. A liquid discharge apparatus according to claim 1, wherein the adjustment unit includes a liquid surface detection unit that detects a position of the liquid surface of the operation liquid in the second reservoir.

3. A liquid discharge apparatus according to claim 2, wherein the adjustment unit includes a third reservoir that stores the operation liquid, a flow path that connects the second reservoir with the third reservoir, a pump that is disposed at the flow path and supplies the operation liquid from the third reservoir to the second reservoir.

4. A liquid discharge apparatus according to claim 1, wherein the flexible member is disposed in the first reservoir along a vertical direction.

5. An imprint apparatus, comprising:

a head including a discharge port surface on which a discharge port is formed to discharge a liquid;

a first reservoir that stores the liquid to be supplied to the head;

a flexible member, separating an inner space of the first reservoir into a first chamber that stores the liquid and a second chamber that stores an operation liquid;

a second reservoir communicating with the second chamber, the second reservoir storing the operation liquid to be supplied to the second chamber, the second reservoir being in such a manner that a liquid surface of the operation liquid stored in the second reservoir is positioned below the discharge port surface;

an adjustment unit that performs adjustment in such a manner that a position of the liquid surface of the operation liquid in the second reservoir falls within a predetermined range in a state where the second reservoir is opened to atmosphere; and

a forming unit configured to bring a surface of a substrate on which the liquid is discharged by the head and a surface of a mold on which an unevenness pattern is formed into contact with each other, so as to form a pattern corresponding to the unevenness pattern of the mold on the surface of the substrate.

6. An imprint apparatus according to claim 5,

wherein the liquid includes a photocurable liquid and

wherein the forming unit includes an irradiation unit that irradiates the pattern formed on the substrate so as to cure the pattern.

7. A part manufacturing method for manufacturing a part including a substrate by using an imprint apparatus including:

a head including a discharge port surface on which a discharge port is formed to discharge a liquid;

a first reservoir that stores the liquid to be supplied to the head;

a flexible member, separating an inner space of the first reservoir into a first chamber that stores the liquid and a second chamber that stores an operation liquid;

a second reservoir communicating with the second chamber, the second reservoir storing the operation liquid to be supplied to the second chamber, the second reservoir being in such a manner that a liquid surface of the operation liquid stored in the second reservoir is positioned below the discharge port surface; and

an adjustment unit that performs adjustment in such a manner that a position of the liquid surface of the operation liquid in the second reservoir falls within a predetermined range in a state where the second reservoir is opened to atmosphere, the method comprising:

applying the liquid to a surface of a substrate by the head;

bringing the surface of the substrate on which the liquid is discharged by the head and a surface of a mold on which an unevenness pattern is formed into contact with each other, so as to form a pattern corresponding to the unevenness pattern of the mold on the surface of the substrate; and

treating the substrate on which the pattern is formed.